

Status of preparation at NCBJ Świerk of lead layer photocathodes for SRF injectors (status in Nov. 2015)

J. Lorkiewicz and R. Nietubyć for Pb layer cathodes collaboration



Narodowe Centrum Badań Jądrowych Świerk

National Centre for Nuclear Research

Contents:

- 1. Reminder: the concept of Nb-Pb hybrid SFR photoinjector**
- 2. Eucard commitments as to photocathodes preparation**
- 3. Selection of deposition procedures: dark current measurement and RF quality tests**
- 4. Direct UHV arc coating combined with pulsed plasma ion irradiation: modelling and computation of pulsed heat flow through a lead layer, optimization of processing parameters**
- 5. Development of instrumentation.**

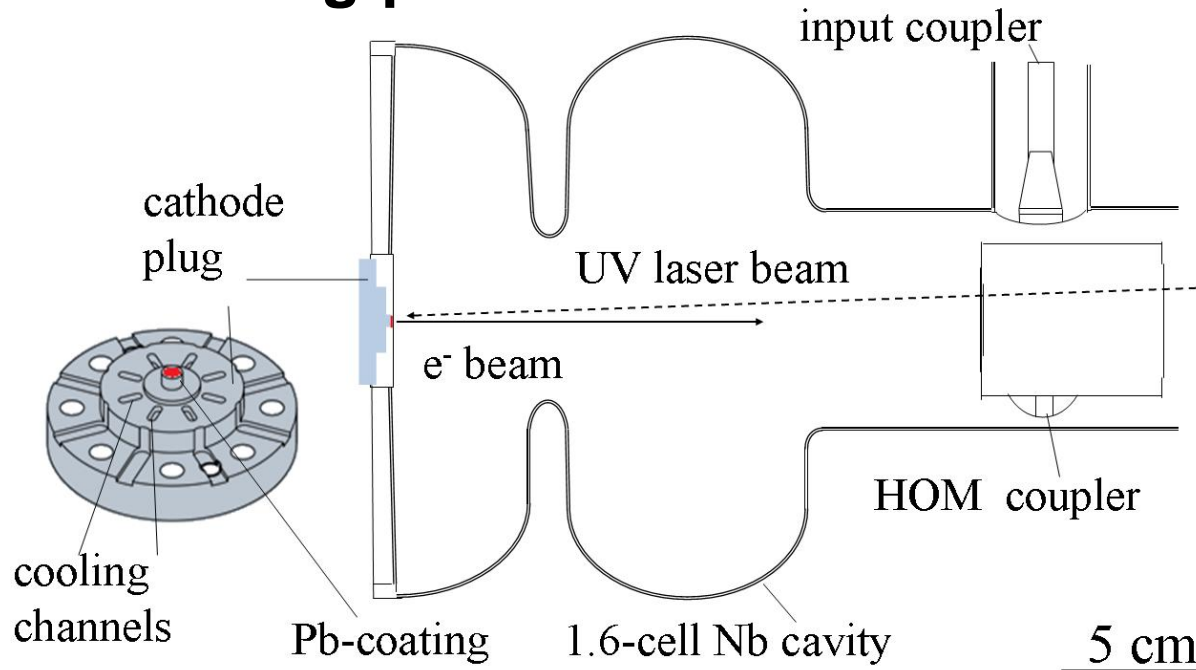
Fully superconducting TESLA/XFEL - type SRF e⁻ injector

1 mA-class electron foto-injector;

$\varepsilon_n < 1 \mu\text{rad}$;

$Q \approx 1 \text{ nC}$,

CW and long-pulsed envisioned



Concept of a Nb-Pb hybrid electron injector with a lead layer photocathode on the rear wall of a 1.6-cell, 1.3 GHz niobium cavity. Pb ($T_c=7.2 \text{ K}$, $B_c \approx 80 \text{ mT}$) is deposited on an exchangeable niobium „plug” integrated with the cavity. Good photoemission characteristics, low dark current and sufficient adhesion are required which is connected with planar surface and low contents of impurities.

Eucard commitments

Workpackage: WP12 Innovative RF technologies

Task: WP12.5 Photocathodes

Milestone

MS80 Demonstrated operation of improved deposition system

M30

Report on samples characterisation NCBJ  delivered Sept. 2015

Pb photocathode deposition for improved performance of SRF guns - deposition improvement, - post-deposition treatment, - Q and QE measurements, dark current reduction

Deliverables

D12.8 Optimised procedure for microdroplets flattening with an UV laser

M36

Report NCBJ

D12.9 Pb/Nb plug photocathodes measurements and characterization.

M42

Report HZDR (+ HZB + DESY + NCBJ)

Collaboration

| NCBJ: | HZB: | HZR: | DESY: | TJNAF: | BNL: |
|---------------|-------------|-------------|---------------|---------------|-------------|
| R. Nietubyć | T. Kamps | J. Teichert | J. Sekutowicz | P. Kneisel | J. Smedley |
| J. Lorkiewicz | R. Barday | R. Xiang | D. Kostin | | |
| R. Mirowski | | | | | |
| M. Barlak | | | | | |
| J. Witkowski | | | | | |
| W. Kosińska | | | | | |
| W. Grabowski | | | | | |
| | | | | | |

Optimization in lead layers coating and processing to reach uniformity, thickness, reduction of macro-particles at a sufficient thickness and adequate adhesion :

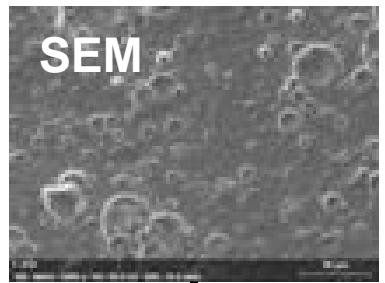
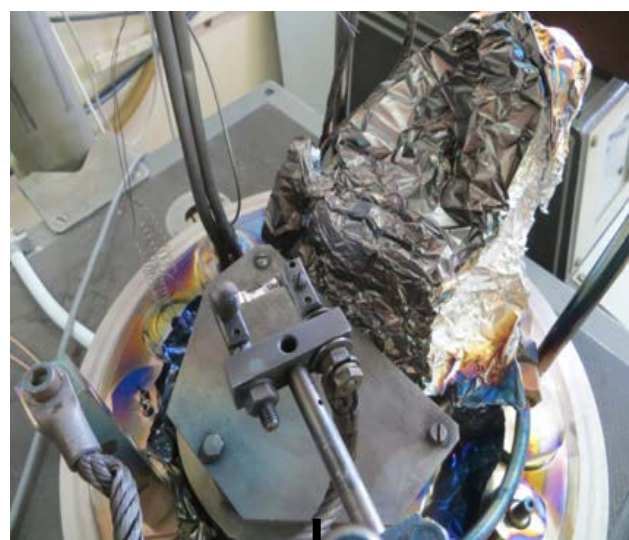
lead coating

extra surface processing

(evaporation)

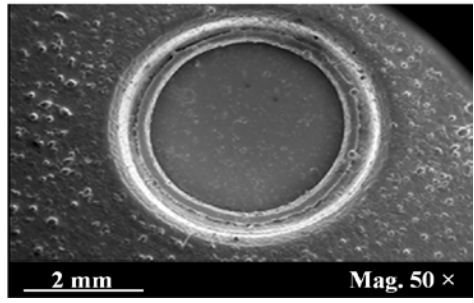
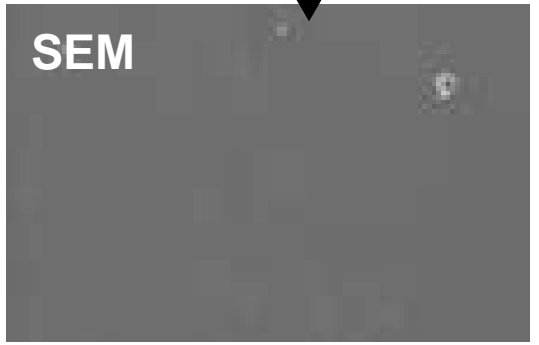
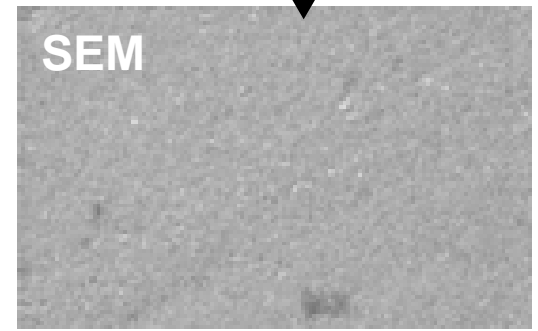
(UHV filtered arc)

(non filtered arc)



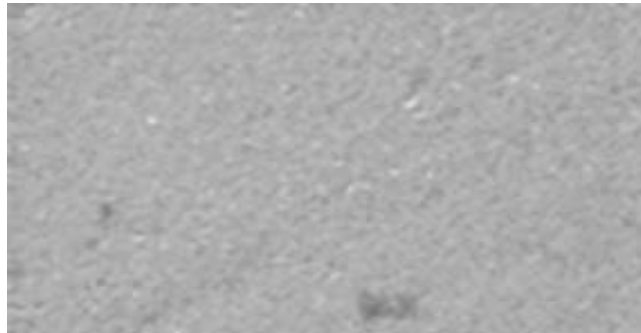
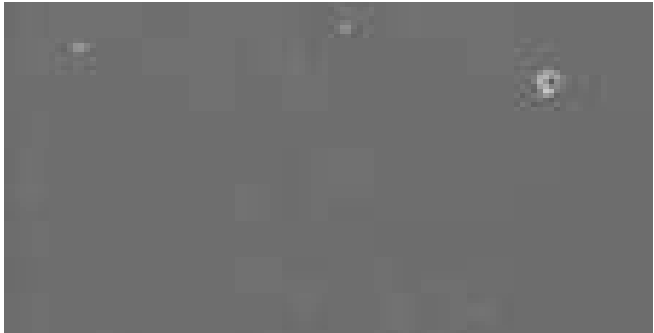
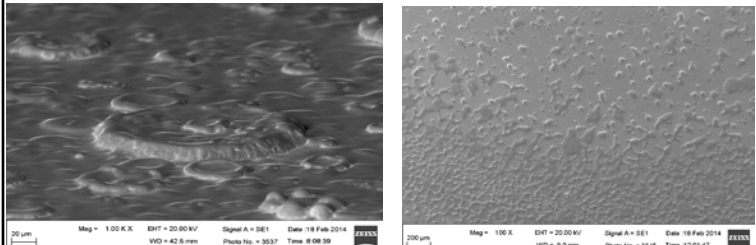
pulsed plasma ion irradiation

**Rod
plasma
injector**



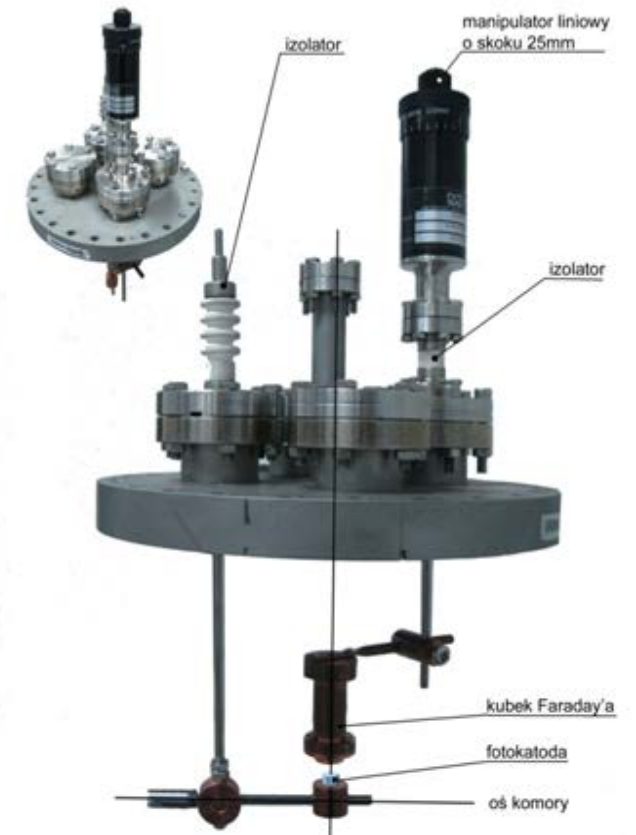
Mag = 1.00 K X EHT = 20.00 kV Signal A = SE1 Det 29 Jul 2015
WD = 10.5 mm Photo No = 8577 Time 14:01:39 ZEISS

Film surface morphology & EDX results

| Coating method | Deposition rate | C, O and N contents (wt %) EDS results | 2 μm Pb layers' morphology and continuity; SEM observations | |
|--|-----------------|--|---|--|
| Evaporation | 60 nm/min | Pb ≈ 90 % C ≈ 3 % O ≈ 3 % N ≈ 2 % |  | Semi-spherical extrusions of diameters < 5 μm density < 50mm ⁻² |
| UHV filtered arc deposition | 200 nm/min | Pb ≈ 93 % C ≈ 2 % O ≈ 1 % |  | Spherical extrusions of diam. up to 40 μm density < 50mm ⁻² |
| UHV non-filtered arc deposition + remelting in pulsed plasma | 3000 nm/min. | Pb ≈ 94 % C ≈ 2 % O ≈ 1 % |  | Numerous massive craters can be flattened at a cost of layer perforation and discontinuity |

Dark current measurements

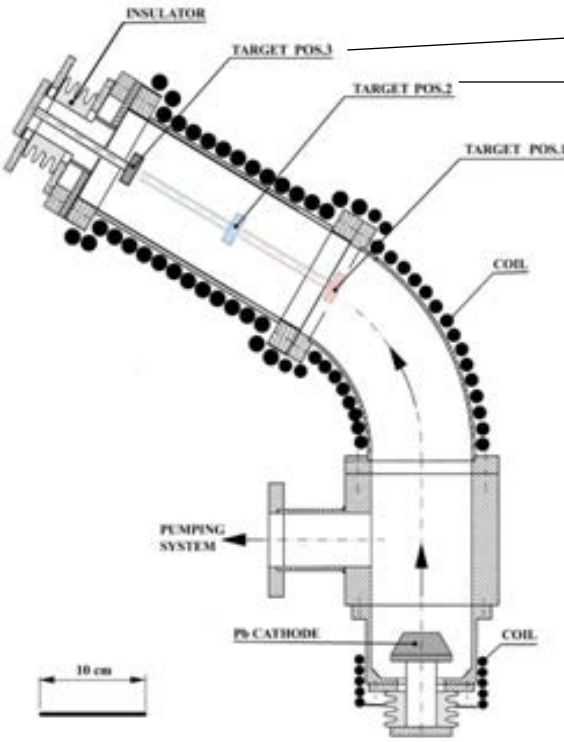
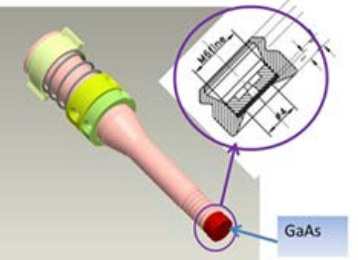
| Cathode preparation | E_{\max} [MV/m] | I_{\max} [nA/cm ²] | E_{\min} [MVm] | I_{\min} [nA/cm ²] |
|---|----------------------|-------------------------------------|---------------------|-------------------------------------|
| UHV filtered arc | 200 | 1600 | 60 | 283 |
| UHV filtered arc + conditioning | 200 | 412 | 60 | 220 |
| UHV non-filtered arc + plasma pulses | 200 | 294 | 60 | 22 |
| Evaporated Pb layer | 200 | 390 | 60 | 60 |
| Evaporated and conditioned Pb layer | 200 | 210 | 60 | 56 |



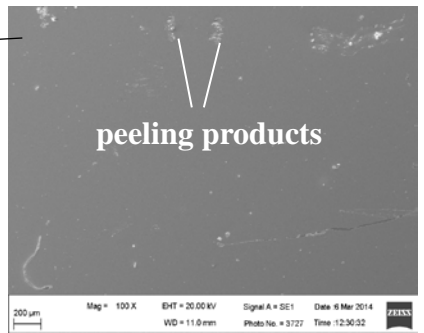
RYS.4 System mocowania układu fotokatoda-kubek Faraday'a

- pulsed dc field in a gap of 100 μm ,
- pulse length 1 μs ,
- duty factor 0.2%.

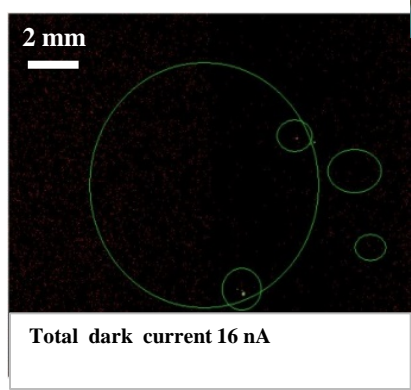
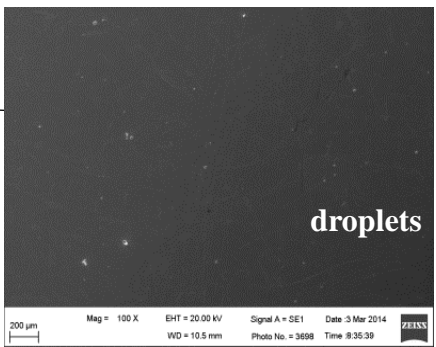
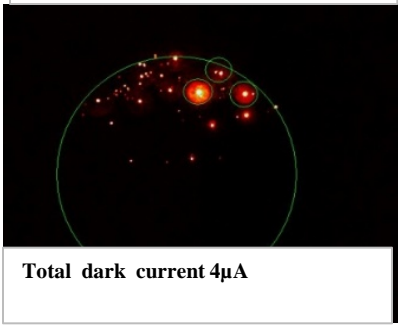
Field emission from filtered-arc coated Pb in dc field



SEM



Field emission mapping



dark current < 50 pA

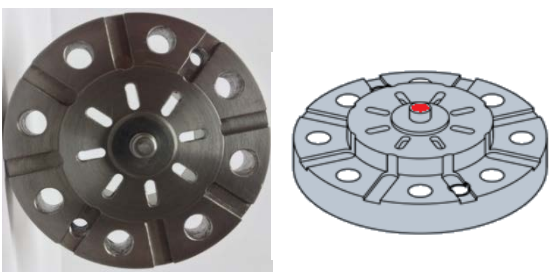
QE measurements (2e-5 to 1e-4) at HZDR – R. Xiang



Emitter Surface scanning and mapping at HZB on three Nb-Pb photocathodes lead coated in filtered arc at NCBJ in a 400 μm in electrostatic field up to 25 MV/m.

- R. Barday
- results non-reproducible, strongly dependent on the target position and on conditioning

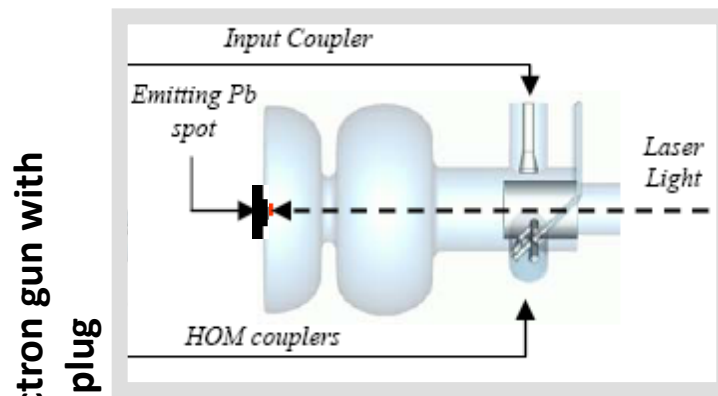
Quality tests of a complete SRF injector with **evaporation-coated Pb cathode**



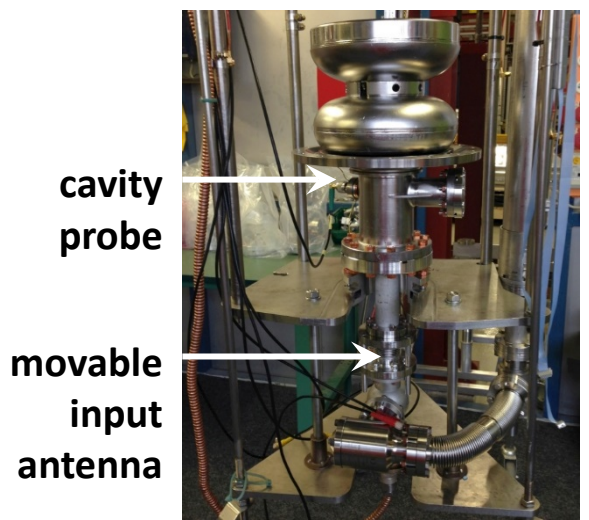
Niobium plug with Pb evaporated on the tip



Evaporated layer, smooth but not adherent and not tight

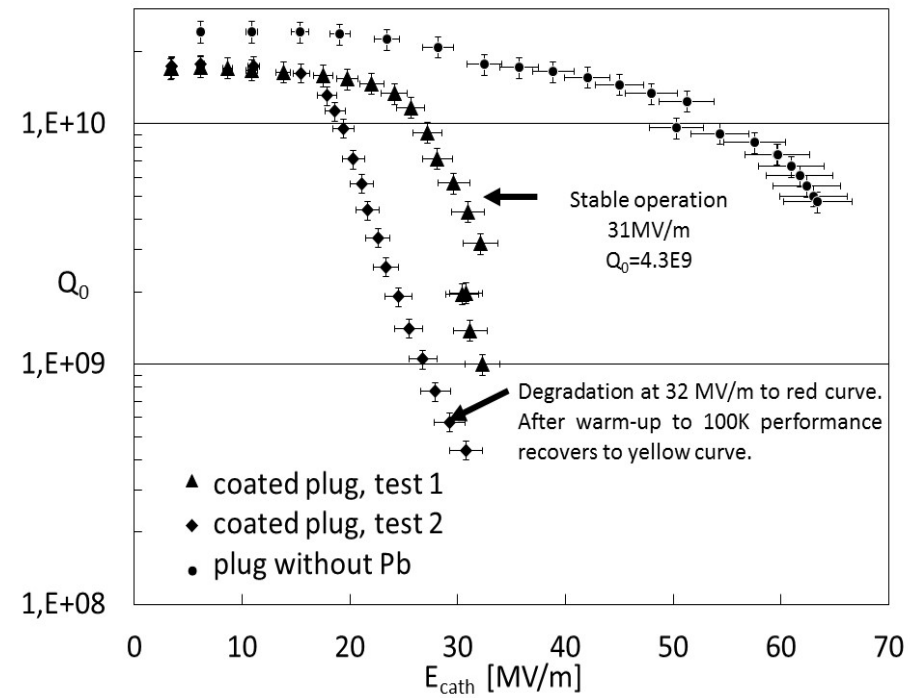


Electron gun with the plug



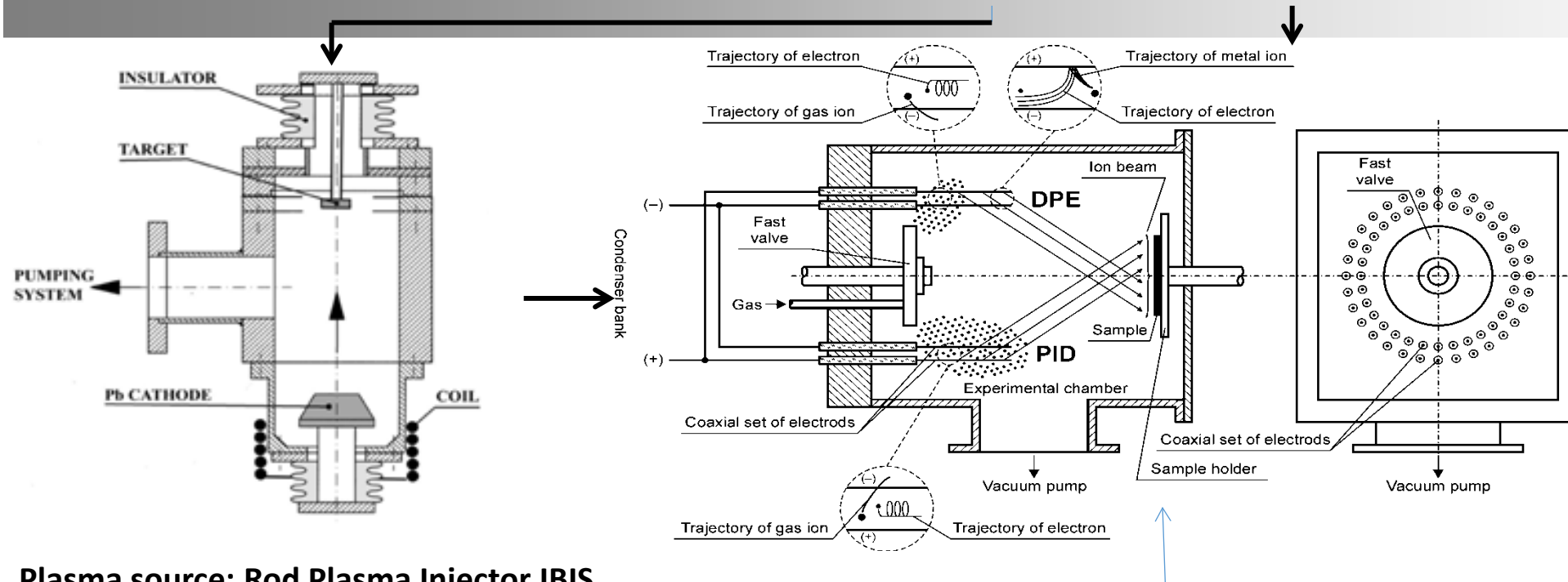
D. Kostin, J. Sekutowicz

Vertical test stand at DESY



Too weak adhesion of Pb layer – the film non-resistant to HPR

First choice for further development: non-filtered Pb coating + remelting in pulsed plasma ion beam



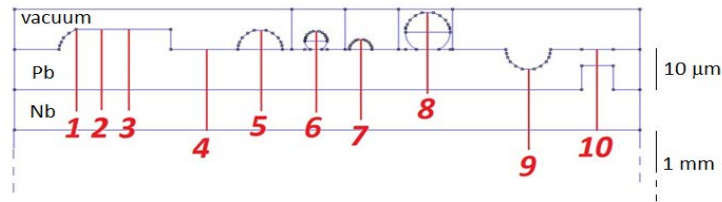
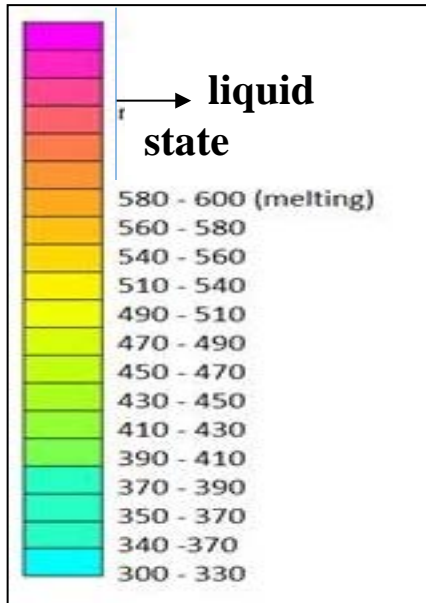
Plasma source: Rod Plasma Injector IBIS

The RPI-IBIS device was equipped with two coaxial electrodes composed of 32 thin metallic rods placed inside a vacuum chamber, which was pumped out to the background pressure equal to about 10^{-6} Pa. Before each discharge the inter-electrode gap was filled up with some amount of Ar injected by a fast acting valve. with a chosen delay advance to the discharge $190 \mu\text{s}$ (pulse implantation doping – PID regime). During the discharge the working gas, after its ionization, was accelerated in the injector and emitted along the z-axis towards Pb/Nb target in a form of an intense plasma-ion stream. The energy spectrum of the ions generated in the rod plasma injector consists of a sharp, gaussian peak which lasts about $1 \mu\text{s}$ and an energetic tail. The average ion energy within this peak falls between several to several tens keV For Pb film processing a single (out of five) capacitor section, charged up to 25-28 kV was used to initiate discharge. A fluency of a single ion pulse measured by a set of thermocouples reached $1 - 1.8 \text{ J/cm}^2$.

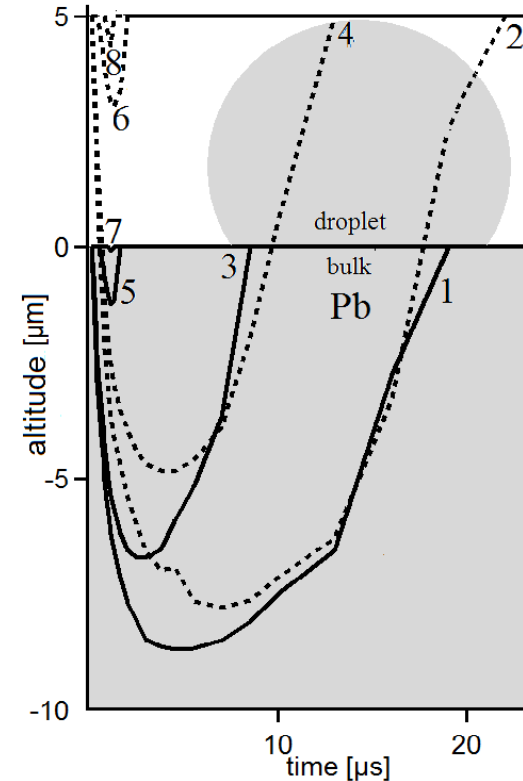
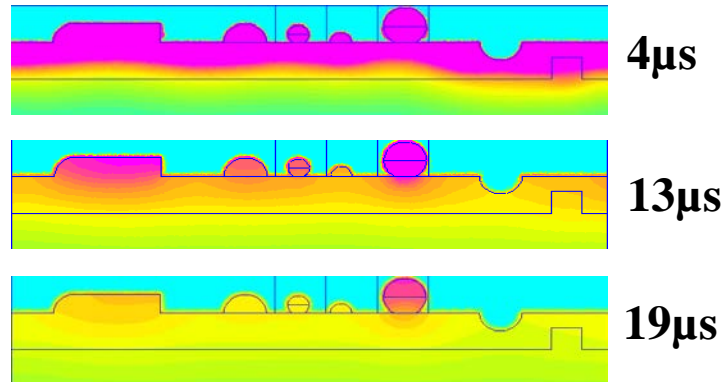
Analysis of thermal evolution within a lead layer on niobium

To avoid a lead film destruction during plasma ion pulse processing which typically results from poor niobium wettability with molten lead, pulsed heat flow through a 10 μm thick Pb layer on Nb was modelled and computed. A numerical heat flow model, proposed by R. Nietubyc in 2014 was further refined so as to reach a better resolution of temperature distribution across a layer. Due to the simplifications assumed the accuracy of calculated results (temperature distribution) is within $\pm 20\%$

Assumed lead layer surface profile



Temperature distribution

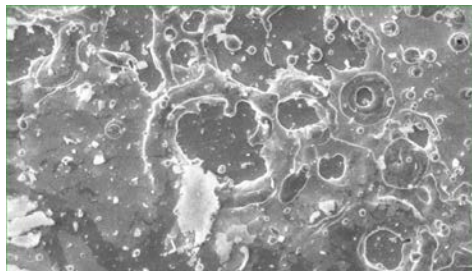


Conclusions:

- At 1.5 J/sqcm bulk Pb is melted down to 9 μm , and under a droplet down to 8 μm , Melting front does not reach Nb-Pb interface.
- Extrusions are in liquid state some μm longer than bulk layer
- At 1 J/sqcm solidification times amount to half of that at 1.5 J. Bulk ablation rate is negligible

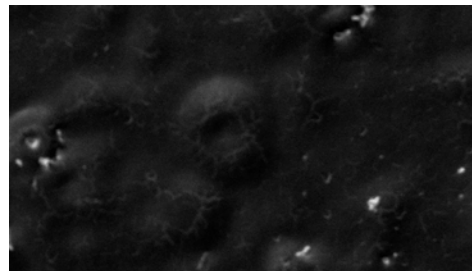
Practical flattening of non-filtered Pb layers of 10-20 μm with $1\mu\text{s}$ Ar plasma pulses

10 μm /(1 \times 1.8 J/sqcm)



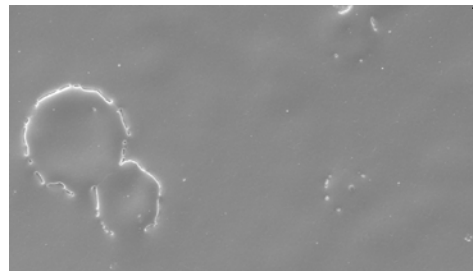
50 μm Mag.

10 μm /(10 \times 1 J/sqcm)

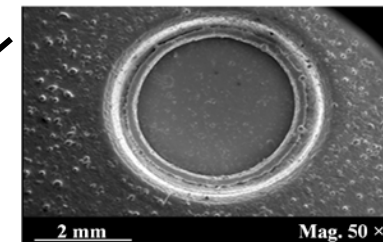


50 μm Mag.

10 μm /(25 \times 1 J/sqcm)

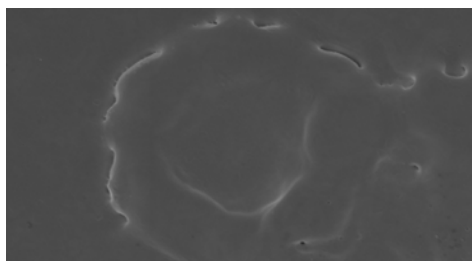


100 μm Mag.



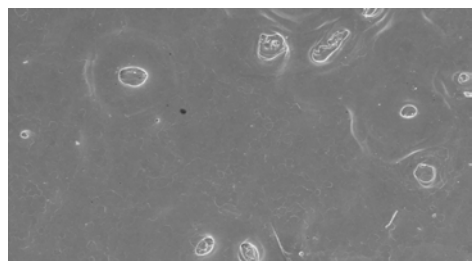
EDX: 3.4 wt% O
2.4 wt %C
3.4 wt % N

(13 μm /2 \times 1.5 J/sqcm)



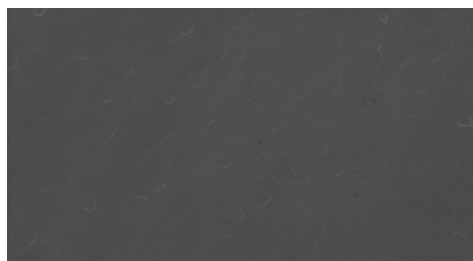
20 μm Mag.

13 μm / 3 \times 1.5 J/sqcm



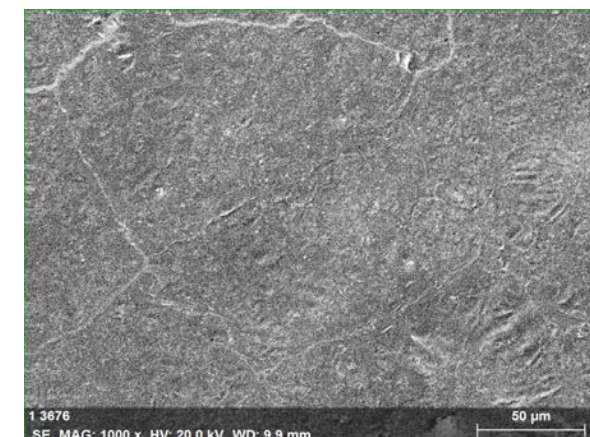
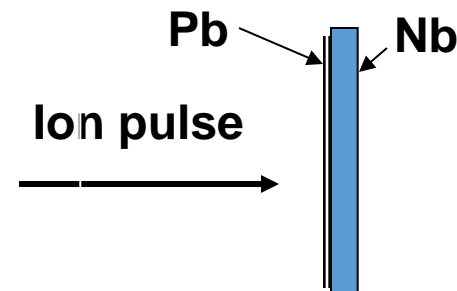
50 μm Mag.

20 μm / 5 \times 1.5 J/sqcm

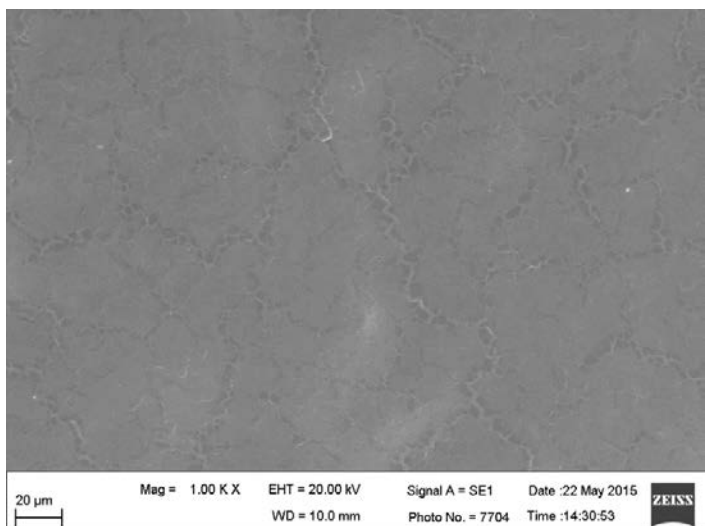


50 μm Mag.

EDX: 1.9 wt% O
2.5 wt %C



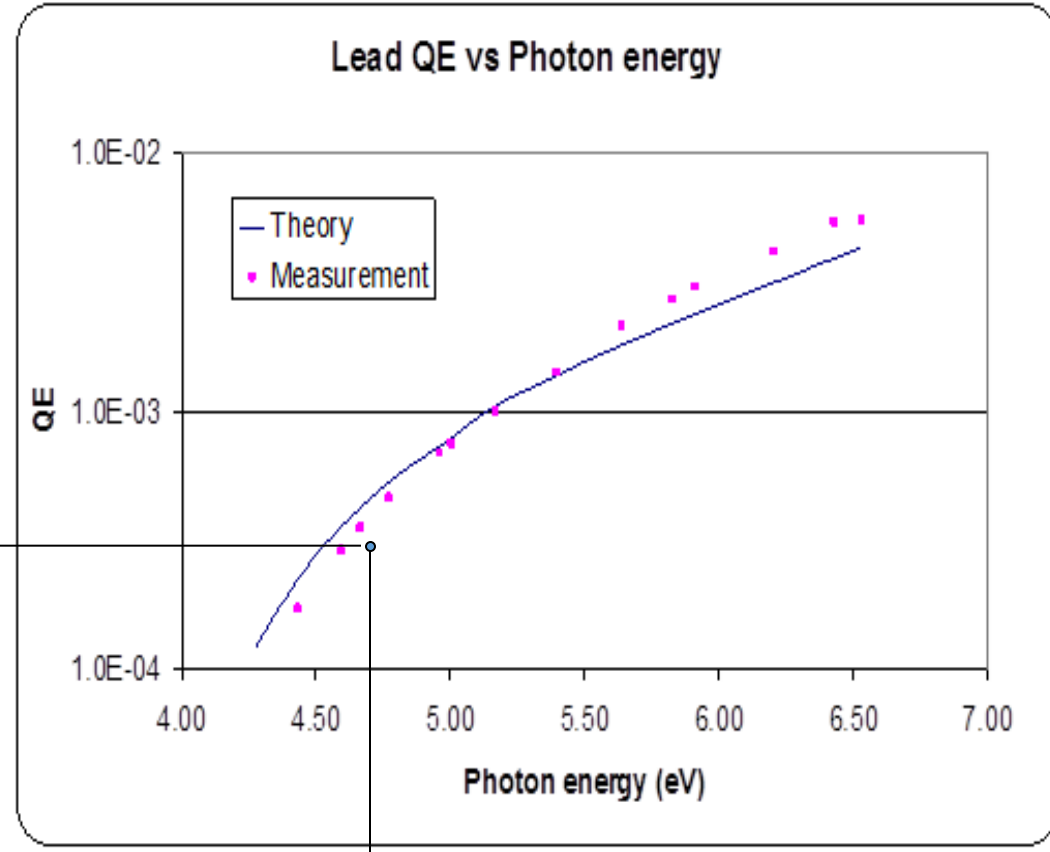
QE measurement from 20 μm thick Pb film on Nb plug; 0.5-cell SRF injector at BNL (Summer 2015)



Aggressive cleaning with 10⁵ pulses of 266 nm laser beam at 60 mJ/cm²



3.0E-4



4.70 eV

J. Smedley, BNL

QE and dark current measurement setup at NCBJ

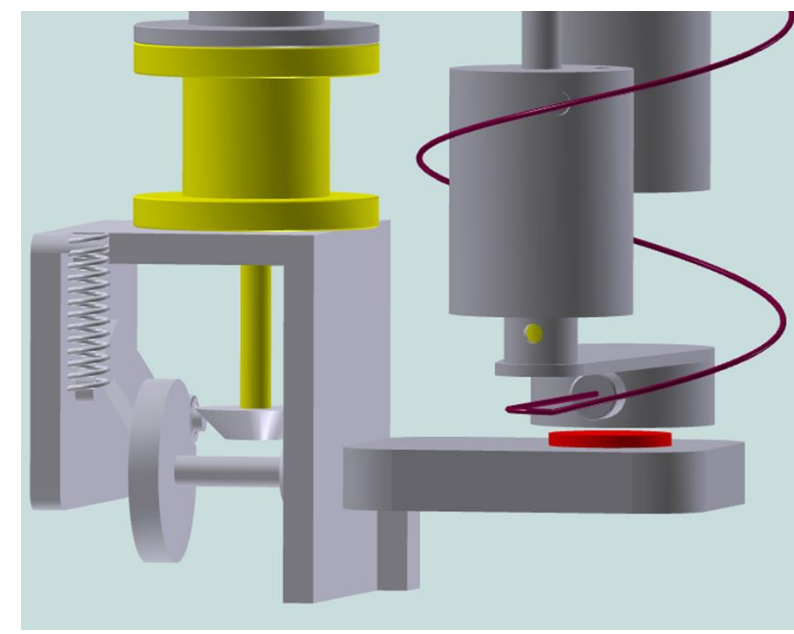
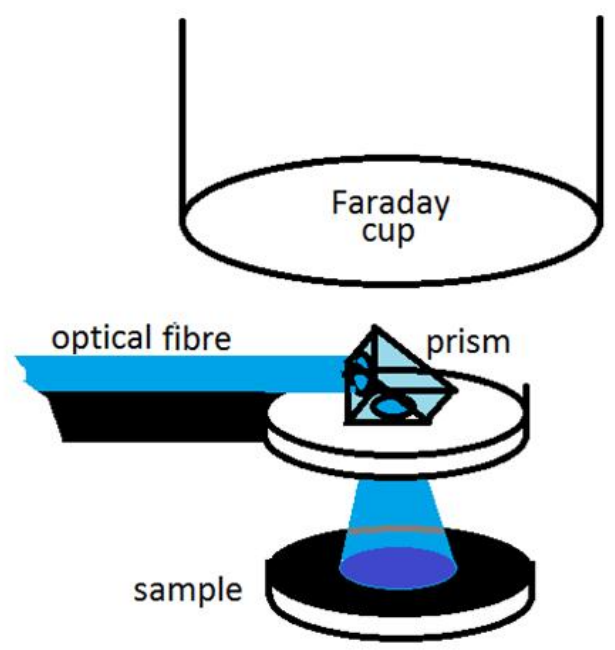
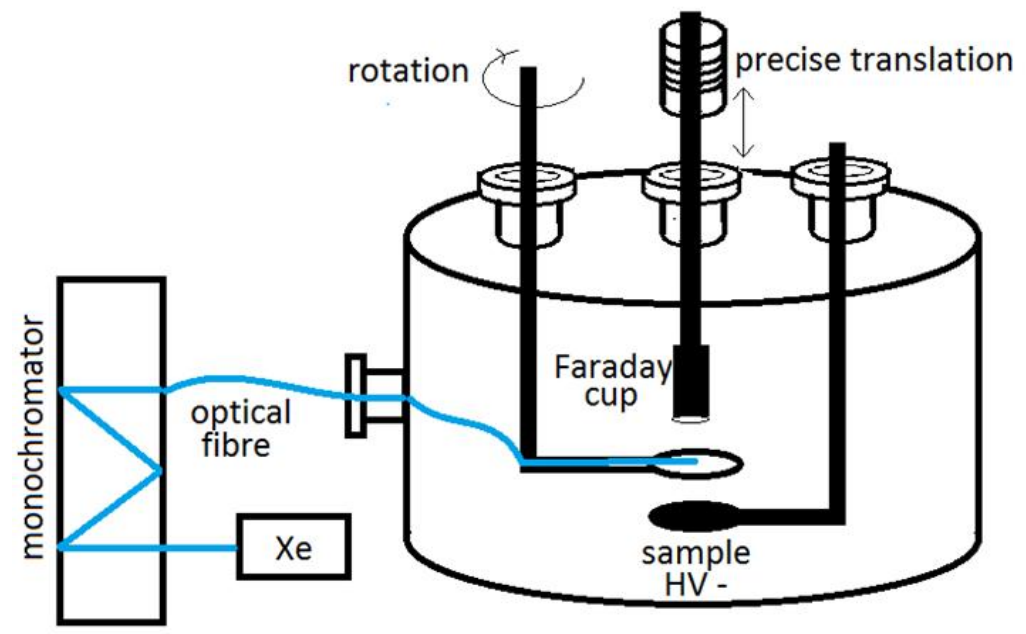
Xenon lamp 150 W,

Czerny-Turner Monochromator,

Optical fiber,

$\Lambda = 190 - 700 \text{ nm}$

—————→ **COMPLETED; to be tested by the end of 2015**



Thank you